

REMARKS

In accordance with the foregoing, claims 4, 10, and 19 have been amended. Claims 11-13 have been cancelled. Claims 4, 5, 7-10 and 14-30 are pending and under consideration. Claims 1-3 are withdrawn from consideration.

The language "on the photoresist" is deleted, thus the rejection under 35 U.S.C. § 112 based on this language is moot.

As for the claimed range between 35 microns and 100 microns, the rejection is respectfully traversed. The Examiner admits that the present Specification discloses a range between 10 and 100 microns. The Examiner insists that the Applicant is bound to also rely upon this range in the claims. However, it is noted that 35 U.S.C. § 112, first paragraph requires a written description in such terms as to enable any person skilled in the art to make and use same. The Specification discloses a range of 10 to 100 microns. Thus, the Specification is enabling to any value within this range, which would include the values between 35 and 100 microns. It is noted that 35 U.S.C. § 112 does not require that the claims correspond exactly to what is disclosed in the Specification.

The rejection based on Chen (U.S. '589) is now discussed. Independent claim 4, used herein as an example, recites a first part having a relatively high UV transmission rate, a second part having a relatively low UV transmission rate and a fourth part having the relatively low UV transmission rate of the second part, the first part being between the fourth and second parts. In contrast, the mask of Chen has an opaque area 142 within a partially opaque area 144. Chen, FIG. 6A. Thus, the opaque area 142 is not between different parts having a same UV transmission rate.

Independent claim 4 further recites an amount of the UV light being between $2\text{mJ}/\text{cm}^2$ and $4000\text{mJ}/\text{cm}^2$ to adjust a hardening depth and wherein the forming of the photo resist includes forming the photo resist to have a thickness from $35\mu\text{m}$ to $100\mu\text{m}$. It is respectfully submitted that Chen does not disclose these features.

Accordingly, withdrawal of the rejection is requested.

There being no further outstanding objections or rejections, it is submitted that the application is in condition for allowance. An early action to that effect is courteously solicited.

Finally, if there are any formal matters remaining after this response, the Examiner is requested to telephone the undersigned to attend to these matters.

If there are any additional fees associated with filing of this Amendment, please charge

the same to our Deposit Account No. 19-3935.

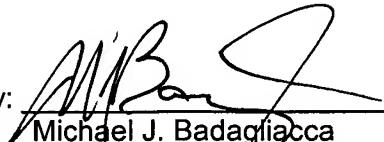
Respectfully submitted,

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